

SEMICONDUCTOR Batch S



Wet bench for semiconductor manufacturing and other applications

Modular & Customised

Areas of application

- Semiconductor, MEMS, LED, OLED, Optoelectronics, Plastic Electronics
- All wet process applications in FEOL and BEOL

Features and benefits

- High process flexibility and process analysis by freely configurable software
- Advanced scheduling and throughput simulation
- Standard and highly customised systems
- All kind of substrates from 4" up to 12"
- Handling system for standard carrier, low mass carrier and carrierless
- Flexible input / output
- The modular design facilitates minor modifications just as well as serious customisation
- Minimized footprint and quick start up by power and control cabinets integrated into the system body
- System sectioned to minimize installation effort and to allow shipping by air or sea freight
- Manufactured according to SEMI standards
- Clean room class up to ISO class 2
- Easy maintenance integral part of design





Technical Data Batch S

Process capabilities	<ul style="list-style-type: none"> • High uniformity within wafer, within batch, run to run • SOM/SPM, H_3PO_4, KOH, BOE, HF, SC1, SC2, Rinse, Rinse O_3 • Marangoni drying, HF-Ozone drying, hot water drying 		
Manufacturing capabilities	<ul style="list-style-type: none"> • E-MTBFp > 500h • Uptime > 96% • Advanced process control and manufacturing - FDC, R2R Control, EHM, real-time data collection 		
Dimensions	Width* 2100 mm * for special applications width can be adapted	Height including flow box 2900 mm	Length according to process specification
Options	<ul style="list-style-type: none"> • Extended loading/unloading buffer station • Customised process carriers • Storage tanks for each chemical and process module decouple dosing from external/central supply of chemicals • Bulk chemical supply systems 		